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Vacuum, Surfaces, and Films

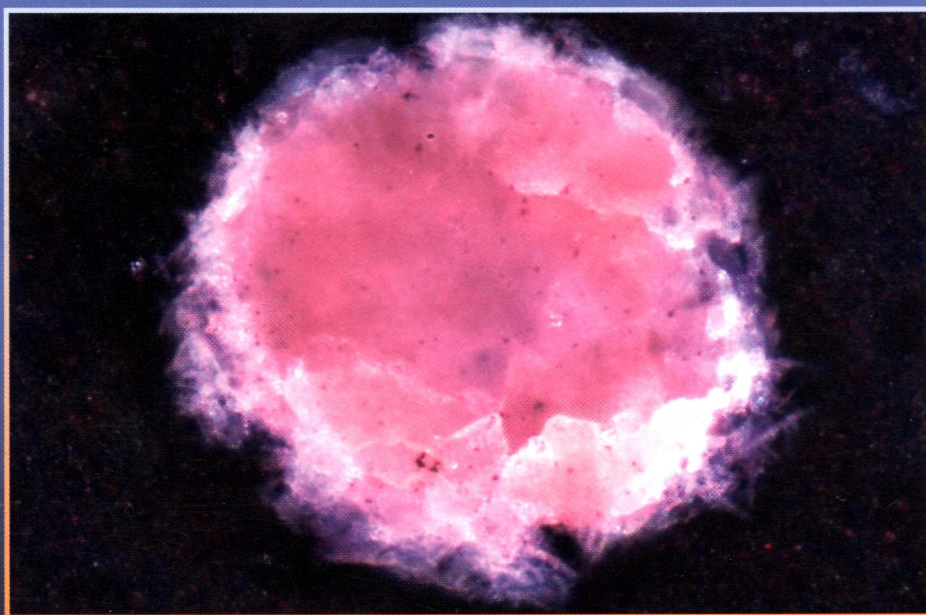


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Review Article:

Atmospheric-pressure Low-temperature Plasma Processes for Thin Film Deposition

-by Hiroaki Kakiuchi, Hiromasa Ohmi, and Kiyoshi Yasutake



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Vacuum, Surfaces, and Films

JVST A

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On The Cover: *Martin Brierley, John Knowles, Neil Montgomery, and Michael Preuss, JVST A 32(3), p. 031402-1 (2014). Cover shows a top down optical micrograph of a cerium hydride growth site (ca 50 μm diameter) taken using bright field illumination on a Zeiss AxioImager M1m.*